Form 1449*

Atty. Docket No.: 303.676US2

Serial No. Unknown

INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Use several sheets if necessary)

Applicant: Gurtej Singh Sandhu et al.

Filing Date: Herewith

Group: Unknow:

U.S. PATENT DOCUMENTS

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**Examiner Initial	S W	Date:	Name	01	0.4.1	Filing Date U
Initial	Document Number	Date	Name	Class	Subclass	If Appropriate
IV	3,900,312	08/19/1975	Terry, J.C., et al.	75	68 B	10/16/72
	4,340,617	07/20/1982	Deutsch, et al.	427	53.1	05/19/80
	4,343,870	08/10/1982	Heller, A., et al.	429	111	09/08/80
	_ 4,359,490	11/16/1982	Lehrer, W.I.	427	95	07/13/81
	_ 4,713,258	12/15/1987	Umemura	427	35	07/03/85
	_ 4,721,631	01/26/1988	Endo, et al.	427	66	03/09/87
	_ 4,751,101	06/14/1988	Joshi, R.V.	427	39	04/30/87
	_ 4,868,005	09/19/1989	Ehrlich, et al.	427	53.1	03/10/88
	4,876,112	10/24/1989	Kaito, et al.	427	38	03/27/87
	4,884,123	11/28/1989	Dixit, P., et al.	357	71	02/19/87
	_ 4,923,717	05/08/1990	Gladfelter, et al.	427	252	03/17/89
	_ 4,957,777	09/18/1990	Ilderem, V., et al.	427	55	10/12/89
	_ 4,971,655	11/20/1990	Stefano, et al.	156	659.1	12/26/89
	_ 5,005,519	04/01/1991	Egermeier, et al.	118	722	03/14/90
1	E 01E 220	05/14/1991	Okumura, K., et al.	156	643	02/28/90
	_ 5,013,330	06/11/1991	Grundy, et al.	65	60.51	10/12/89
	_ 5,032,233	07/16/1991	Yu, C., et al.	204	192.28	09/05/90
	_ 5,049,975	09/17/1991	Ajika, N., et al.	357	71	03/12/90
	<u> </u>	06/23/1992	Sandhu, G.S., et al.	357	67	06/10/91
<u></u>	_ 5,136,362	08/04/1992	Grief, et al.	357	67	11/27/90
	_ 5,147,819	09/15/1992	Yu, C., et al.	437	173	02/21/91
	_ 5,173,327	12/22/1992	Sandhu, G.S., et al.	427	573	06/18/91
	5 192 589	03/09/1993	Sandhu, G.S.	427	255.1	09/05/91
	_ 5,192,369	03/23/1993	Doan, T.T., et al.	437	41	04/06/92
	_ 5,202,579	04/13/1993	Fujii, H., et al.	257	751	01/21/92
	5,227,331	07/13/1993	Westmoreland, D.	437	174	02/10/92
	_ 5,227,334	07/13/1993	Sandhu	437	190	10/31/91
- 1	5 232 873	08/03/1993	Geva, M., et al.	437	192	10/13/92
	_ 5,240,739	08/31/1993	Doan, T., et al.	427	126.1	08/07/92
	_ 5,246,881	09/21/1993	Sandhu, G.S., et al.	437	192	04/14/93
	_ 5,252,518	10/12/1993	Sandhu, et al.	437	200	03/03/92
	_ 5,254,499	10/19/1993	Sandhu, G., et al.	437	192	07/14/92
	_ 5,258,096	11/02/1993	Sandhu, et al.	156	643	08/20/92
	_ 5,273,783	12/28/1993	Wanner	427	250	03/24/93
	_ 5,275,715	01/04/1994	Tuttle	205	123	01/23/92
	_ 5,278,100	01/11/1994	Doan, T.T., et al.	437	200	11/08/91
	_ 5,306,951	04/26/1994	Lee, et al.	257	755	05/14/92
	_ 5,320,880	06/14/1994	Sandhu, G.S., et al.	427	578	11/18/93
	_ 5,341,016	08/23/1994	Prall, K.D., et al.	257	412	06/16/93
	_ 5,344,792	09/06/1994	Sandhu, G.S., et al.	437	200	03/04/93
TV	_ 5,344,792 _ 5,374,591	12/20/1994	Hasegawa, T., et al.	437	187	03/23/92
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Form 1449*

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U.S. PATENT DOCUMENTS

U.S. PATENT DOCUMENTS						
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
IV	_ 5,376,405	12/27/1994	Doan, T., et al.	427	126.1	04/15/93
01	_ 5,381,302	01/10/1995	Sandhu, G., et al.	361	305	08/10/93
	_ 5,384,284	01/24/1995	Doan, T.T., et al.	437	190	10/01/93
	5,384,289	01/24/1995	Westmoreland, D.L.	437	245	06/17/93
	_ 5,391,410	02/21/1995	Nii, T., et al.	427	578	05/28/93
	_ 5,393,564	02/28/1995	Westmoreland, et al.	427	248.1	05/02/94
	_ 5,399,379	03/21/1995	Sandhu	427	255.2	05/11/94
	_ 5,416,045	05/16/1995	Kauffman, et al.	437	174	02/18/93
	5,425,392	06/20/1995	Thakur, et al.	437	173 ·	05/26/93
	_ 5,453,640	09/26/1995	Kinoshita, Y.	257	520	12/20/94
	_ 5,459,353	10/17/1995	Kanazawa, M.	257	751	01/05/95
L	_ 5,496,762	03/05/1996	Sandhu, et al.	437	60	06/02/94
	_ 5,506,166	04/09/1996	Sandhu, G.S., et al.	437	60	09/27/94
	_ 5,508,066	04/16/1996	Akahori, T.	427	571	09/14/94
	_ 5,567,243	10/22/1996	Foster, R.F., et al.	118	730	06/06/95
	_ 5,571,572	11/05/1996	Sandhu, G.	427	585	06/30/94
	_ 5,575,708	11/19/1996	Chau, S., et al.	451	305	07/07/95
•	_ 5,595,784	01/21/1997	Kaim, R., et al.	427	255.2	08/18/95
	_ 5,607,722	03/04/1997	Vaartstra, et al.	427	248.1	02/09/96
	_ 5,633,200	05/27/1997	Hu, Y.	438	653	05/24/96
	_ 5,641,545	06/24/1997	Sandhu, G.S.	427	573	06/07/95
	_ 5,644,166	07/01/1997	Honeycutt, J., et al.	257	754	07/17/95
	_ 5,693,557	12/02/1997	Hirao, S., et al.	437	60	01/24/96
	_ 5,747,116	05/05/1998	Sharan, S., et al.	427	534	01/16/96
	_ 5,773,890	06/30/1998	Uchiyama, T., et al.	257	753	08/27/96
	_ 5,828,131	10/27/1998	Cabral, Jr., C., et al.	257	757	01/16/96
	_ 5,834,371	11/10/1998	Ameen, M.S., et al.	438	656	01/31/97
	_ 5,838,052	11/17/1998	McTeer, A.	257	437	03/07/96
	_ 5,956,595	09/21/1999	Zenke, M.	438	398	07/15/97
	_ 5,973,402	10/26/1999	Shinriki, H., et al.	257	768	01/30/97
	_ 5,976,976	11/02/1999	Doan, T.T., et al.	438	683	08/21/97
	_ 6,031,288	02/29/2000	Todorobaru, H., et al.	257	754	11/12/96
	_ 6,120,844	09/19/2000	Chen, L., et al.	427	255.28	03/27/96
71/	_ 6,143,362	11/07/2000	Sandhu, G.S., et al.	427	255.391	02/25/98

FOREIGN PATENT DOCUMENTS

**Examiner						Translation
Initial	Document Number	Date	Country	Class	Subclass	Yes No
	. 0798777	10/01/1997	European	H01L	21/768	
	. 8-176823	07/09/1996	Japan	C23C	16/02	
	. 98/34445	08/06/1998	PCT	H05K	3/26	

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Jeff Vorheats

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n Inibécèment Number	Date	Country	Class	Subclass	Yes
No					

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

**Examiner Initial	(Including Author, Title, Date, Pertinent Pages, Etc.)
12	Bachmann, P., et al., "Plasma-Assisted Chemical Vapor Deposition Processes", MRS Bulletin, 52-59, (December 1988)
	Bouteville, A., et al., "TiSi2 Selective Growth in a rapid thermal low pressure chemical vapor depositoin system", <u>Journal of the Electrochemical Society</u> , 139, 2260-2263, (August 1992)
	Cowher, M., et al., "Low Temperature CVD Garnet Growth", <u>Journal of Crystal</u> <u>Growth, 46</u> , 399-402, (1979)
	Engqvist, J., et al., "Selective deposition of TiSi2 from H2-TiCl4 Gas mixtures and si: Aspects of Thermodynamics including Critical evaluation of thermochemical data in the Ti-Si System", <u>Journal of the Electrochemical Society</u> , 139, 3197-3205, (November 1992)
	Esquivel, A., et al., "Electrical and Physical Characteristics of Dry Oxygen, High Pressure Oxidation for SUB-0.5 um CMOS Isolation", Abst. Int'l Electron Devices Meeting, (1994)
	Herman, I., "Laser-Assisted Deposition of Thin Films from Gas-Phase and Surface-Adsorbed Molecules", Chem. Rev., 89, 1323, 1346-1349, (1989)
	Ilderem, V., et al., "Optimized Deposition Parameters for Low Pressure Chemical Vapor Deposited Titanium Silicide", <u>J. Electrochemical Soc. : Solid State Science and Technology</u> , 2590-2596, (Oct. 1988)
	Lee, J., et al., "Plasma enhanced chemical vapor deposition of blanket TiSi2 on oxide patterned wafers", <u>Journal of the Electrochemical Society</u> , 139, 1159-1165, (April 1992)
	Lie, L., et al., "High Pressure Oxidation of Silicon in Dry Oxygen", <u>J.</u> <u>Electrochemical Soc.</u> : Solid State Science and Technology, 129, 2828-2834, (Dec. 1982)
	Moeller, T., et al., "Semiconducting Elements, Ch. 30", <u>In: Chemistry with</u> <u>Inorqanic Qualitative Analysis</u> , 2nd Edition, Academic Press, 995-996, (1984)
TV	Morosanu, C., <u>Thin Films by Chemical Vapor Deposition</u> , Elsevier, N.Y., 42-54 & 460-475, (1990)

Examiner	11	Date Considered	7-5-02
*Substitute Disclosur	edStatement Form (PTO-1449)		

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OTHER DOCUMENTS

	Olima Docommiss
**Examiner	(Including Author, Title, Date, Pertinent Pages, Etc.)
Initial	

17	Panson, A., et al., "Chemical Vapor Deposition of YBa(2)Cu(3)O(7) Using Metalorganic Chelate Precursors", Appl. Phys. Lett., 53, 1756-1758, (October 1988)
4	Rosler, R., et al., "Plasma-Enhanced CVD of Titanium Silicide", <u>J. Vacuum Science Tech.</u> , B2(4), 733-737, (October/December 198)
	Wolf, S., <u>Silicon Processing for the VLSI Era, Vol. 2: Process Integration</u> , Lattice Press, Sunset Beach, California, 202-203, (1990)
TY	Yu, M., et al., "Surface Chemistry of the WF(6)- Based Chemical Vapor Deposition of Tungsten", IBM J. Research Development, 34, 875-883, (November 1990)

Date Considered Examiner

*Substitute Discours Statement Form (PTO-1449)